

# 17th International Conference Reliability and Stress-Related Phenomena in Nanoelectronics „Stress workshop“

## Conference Programm

Monday 24th April 2023

Chair: Ehrenfried Zschech		Session 1: Reliability in micro- and nanoelectronics
08:45	Ehrenfried Zschech deepXscan, Dresden, Germany	<i>Opening remarks</i>
T1	09:00 Sandrine Lhostis STMicronics, France	<i>New reliability challenges for 3D integration stacking using hybrid bonding</i>
T2	09:30 Susann Rothe Technical University Dresden, Germany	<i>Combined Modeling of Electromigration, Thermal and Stress Migration in AC Interconnect Lines</i>
T3	10:00 Ingrid de Wolf, Vladimir Chairman IMEC, Leuven, Belgium	<i>FinFETs: Sensing and feeling mechanical stress</i>
10:30 – 11:00 Break		
Chair: Carl V. Thompson		Session 2: Impact of stress on device properties
T4	11:00 Kristina Kutukova deepXscan, Dresden, Germany	<i>In-situ nano-XCT study of the local energy release rate for crack propagation in advanced ICs</i>
T5	11:30 Pal Jen Wei Bruker, Taiwan	<i>Indentation-Induced Delamination and Adhesion Work Evaluation at Elevated Temperature in Semicon Industrial Cases</i>
T6	12:00 André Clausner Fraunhofer IKTS, Dresden, Germany	<i>Studying stress effects in transistor channels by nanoindentation with varied contact geometries</i>
T7	12:30 Reinhold Dauskardt Stanford University, Palo Alto/CA, USA	<i>Hybrid Dielectric Films for Device Technologies: Understanding Relationships between Molecular Structure, Processing and Function</i>
13:00 – 14:30 Lunch Break		
Chair: Reinhold Dauskardt		Session 3: Robustness of engineered systems: From design to application
T8	14:30 Vikas Tapan Siemens, Munich, Germany	<i>Early architectural exploration with PAVE360</i>
T9	15:00 Hiroshi Nishikawa Osaka University, Japan	<i>Solid-phase bonding process using nanostructured surface for power devices in automotive</i>
15:30	Chair: Kristina Kutukova	<i>Poster Session</i>
17:00	Moderators: <ul style="list-style-type: none"> <li>Andreas Aal, VOLKSWAGEN</li> <li>Oliver Aubel, GLOBALFOUNDRIES</li> </ul> Key Contributors: <ul style="list-style-type: none"> <li>Joe McPherson</li> <li>Günter Haas, Entegris</li> <li>Tapan Vikas, SiemensEDA</li> <li>Nir Sever, proteanTecs</li> </ul>	<i>Podium discussion „Reliability of automotive electronics“</i>  Context: <i>Upcoming hardware challenges on the way towards the Software-defined-Vehicle</i>
19:00 BBQ		

Tuesday 25th April 2023

Chair: Christoph Gammer		Session 4: Materials characterization for device development and reliability engineering
T10	09:00 Iuliana Panchenko Technical University Dresden, Germany	<i>Hybrid bond and nanowired bump technologies for high density interconnect formation on wafer level</i>
T11	09:30 Olivier Thomas, Aix Marseille University, France	<i>Phase change materials for embedded memories: in situ investigation of crystallization behavior using synchrotron radiation</i>
T12	10:00 Ehrenfried Zschech, deepXscan, Dresden, Germany	<i>Controlled microcrack steering into toughened regions – What microelectronics can learn from nature?</i>
10:30 – 11:00 Break		
Chair: Rodrigo Martins		Session 5: Degradation mechanisms and materials behavior
T13	11:00 Matthias Stecher Infineon Technologies, Munich, Germany	<i>Degradation mechanisms of 10kV-reinforced isolated gate drivers at high switching frequencies greater than 30kHz</i>
T14	11:30 Carl V. Thompson MIT, Boston/NY, USA	<i>Contrasting Stress Evolution During Lithiation and Delithiation of Different Electrode Materials for Thin Film Batteries</i>
T15	12:00 Robert Filipek AGH Krakow, Poland	<i>Tortuosity and Porosity in Electrochemical Systems – Computed Tomography Based 3D Transport Modelling</i>
T16	12:30 Jörg Acker Brandenburg University of Technology Cottbus-Senftenberg, Germany	<i>Reliability and Recycling of Battery Materials</i>
13:00 – 14:00 Lunch Break		
14:00 <i>Hiking tour in Saxonian Switzerland</i>		
17:30	Chair: Kristina Kutukova	<i>Poster Session</i>
20:00 Conference Dinner		



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Wednesday 26th April 2023

Chair: André Clausner		Session 6: Micro- and nanomechanics	
T17	09:00	Lionel Vignoud CEA-LETI, Grenoble, France	<i>Strains and stresses control in microelectronic devices: How to optimize the steps from design to manufacturing?</i>
T18	09:30	Daniel Nemecek TESCAN, Brno, Czech Republic	<i>Advancing nanoscale characterization of semiconductor devices by effortless 4D-STEM workflows</i>
T19	10:00	Christoph Gammer, ESI Leoben, Austria	<i>Recent advances in nanoscale strain mapping using 4D STEM</i>
10:30 – 11:00		Break	
Chair: Olivier Thomas		Session 7: Reliability of organic electronics	
T20	11:00	Rodrigo Martins Uninova Lisbon, Portugal	<i>Eco-Strategies for next generation electronics</i>
T21	11:30	Wiebke Langgemach Fraunhofer FEP, Dresden, Germany	<i>Processing flexible glass – thin film stress and its influence on glass durability</i>
T22	12:00	Karl Leo Technical University Dresden, Germany	<i>Organic semiconductors – from a lab curiosity to serious applications</i>
	12:30	Ehrenfried Zschech deepXscan, Dresden, Germany	<i>Closing remarks</i>
13:00 – 14:00		Lunch Break	

## Poster session

Monday, 24th April 2023 15:30 and Tuesday, 25th April 2023 17:30

Poster	Author	Title
P1	Susann Rothe	<i>A Proactive Design Approach to Avoid Migration-Induced Failure in IC Interconnects</i>
P2	Verena Hein	<i>The Influence of the Interconnect Material on the Performance of a Highly Robust Metallization Layout</i>
P3	Stefan Weitz	<i>Micromechanical in-situ studies of on-chip interconnect stack structures using X-ray microscopy</i>
P4	Michael Reisinger	<i>Characterization of the thermo-mechanical behavior of Cu metallization in microelectronic applications</i>
P5	Tobias Ziegelwanger	<i>Local gradients of microstructure and residual stresses in Si device sidewalls separated by laser dicing</i>
P6	André Lange	<i>Investigating HCI and BTI degradation in 4H-SiC CMOS</i>
P7	Jolanta Janczak-Rusch	<i>Nanomultilayers for thermal management and micro-/nano-joining</i>
P8	Bastian Rheingans	<i>Thin-film transfer by nanopaste sinter-bonding</i>
P9	Bowen Zhang	<i>In-situ TEM study and nanomechanical characterization of fracture behavior in two-dimensional covalent organic frameworks</i>
P10	Thomas Langner/Jörg Acker	<i>Shaping the topography of solar wafers due to increased reactivity of lattice strained silicon</i>
P11	Thomas Langner/Jörg Acker	<i>Deposition of copper in lithium-ion batteries during the deep discharge process</i>
P12	Thomas Langner/Jörg Acker	<i>Degradation of Cathode Foils from Lithium-Ion Batteries in Humid Atmosphere</i>